Supplementary Information

Non-stoichiometry and its implications for the properties of PMN-PT thin films

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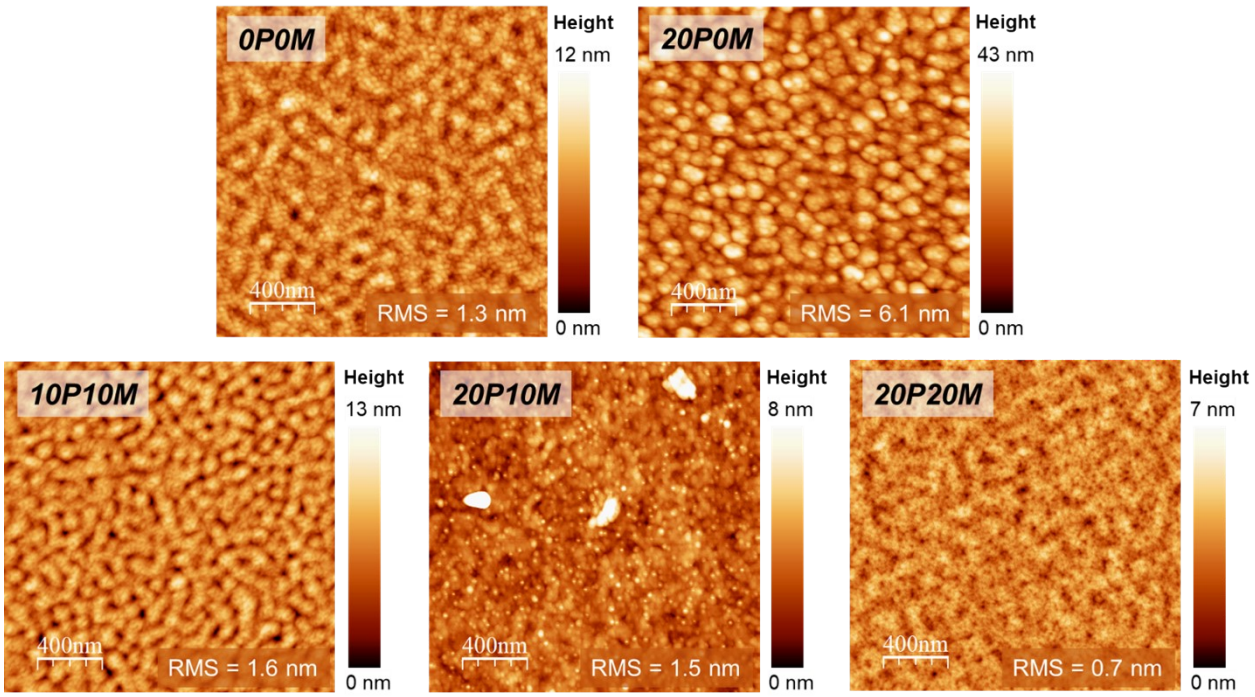
S1: FWHM values, *a* and *c* values from RSMs and calculated a_{pc} values

Sample name	FWHM (*θ*-2*θ*)	*a*	*c*	a_{pc}	FWHM (RC)
0P0M	0.064	4.029	4.014	4.024	0.29
20P0M	0.148	4.026	4.024	4.025	0.42
10P10M	0.066	4.027	4.024	4.026	0.28
20P10M	0.103	4.019	4.028	4.022	0.38
20P20M	0.084	4.020	4.026	4.022	0.30

S2: AFM micrographs of the PMN-PT thin films



S3: STEM cross-section of the LNO layer, revealing the RP-type defects